

2023 SNU Data Science Invited Seminar: Industrial AI Technology and Software Platform for Manufacturing



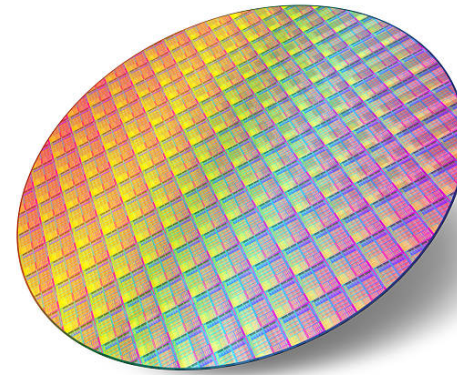
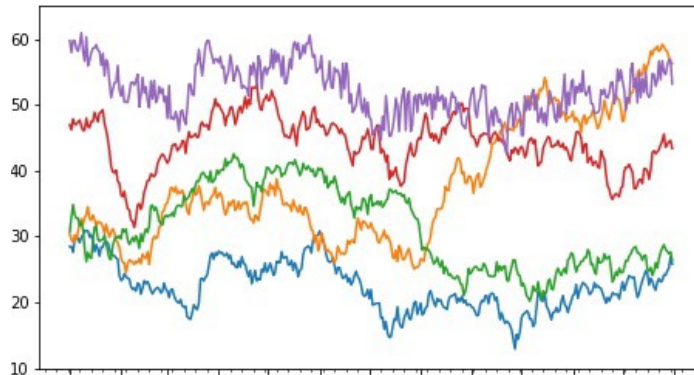
Sunghee Yun

Today

- Why time-series (TS) machine learning in manufacturing AI?
- Machine learning algorithms for TS data
 - supervised learning for time-series
 - time-series anomaly detection
 - uncertainty prediction of predictions
- TS learning applications in manufacturing
 - virtual metrology
 - root cause analysis
- Manufacturing AI Software System
- Conclusion

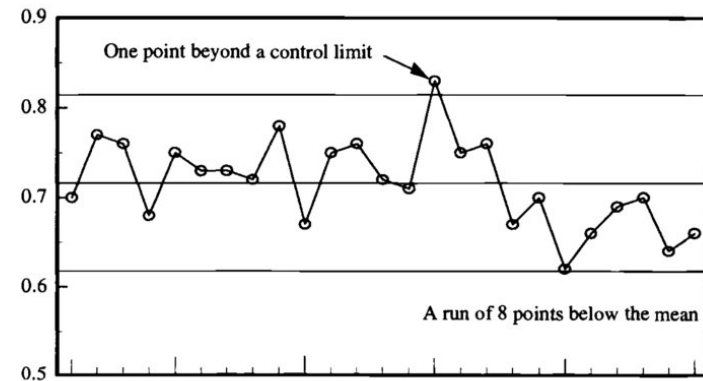
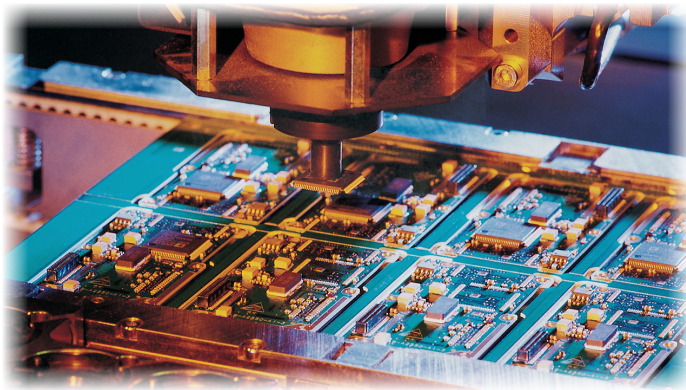
Why time-series (TS) learning?

- (almost) all the data coming from manufacturing environment are TS data
 - sensor data, sound data, process times, material measurement, images, yield, *etc.*
- sheer amount of TS data is huge
 - tera-scale data per day generated in semiconductor manufacturing lines



Why TS learning?

- manufacturing application is about one of the following:
 - prediction of TS values - virtual metrology, yield prediction
 - classification of TS values - equipment anomaly alarms
 - anomaly detection on TS data - root cause analysis, yield analysis



Machine Learning algorithms for TS data

TS data

- definition of times-series:

$$x : T \rightarrow \mathbf{R}^n \text{ where } T = \{\dots, t_{-2}, t_{-1}, t_0, t_1, t_2, \dots\} \subseteq \mathbf{R}$$

- example: material measurements: when $n = 3$

$$x(t) = \begin{bmatrix} \text{thickness}(t) \\ \text{temperature}(t) \\ \text{pressure}(t) \\ \text{feature_size}(t) \end{bmatrix}$$

- for (semi-)supervised learning, we assume two time series

$$x : T \rightarrow \mathbf{R}^n \text{ and } y : T \rightarrow \mathbf{R}^m$$

Time index

- time index does not have to be *time* index
- more general definition

$$x : T \rightarrow \mathbf{R}^n \text{ where } T = \{\dots, s_{-2}, s_{-1}, s_0, s_1, s_2, \dots\}$$

where $\dots < s_{-1} < s_0 < s_1 < \dots$ defines *an* ordering (*e.g.*, total ordering)

- for example, $x(s)$ and $y(s)$ can represent the features and target values for a processed material (*e.g.*, wafer in semiconductor manufacturing), s , where they are not measured at the same time
- (throughout this talk, though, we will use time-index)

Supervised learning for TS

- canonical problem:

predict $y(t_k)$

given $x(t_k), x(t_{k-1}), \dots$ and $y(t_{k-1}), y(t_{k-2}), \dots$

- lots of methods exist depending on assumptions of the data
 - for example, if we assume joint probability distribution of the data, we can have optimal solutions in certain criteria
- however, (in this talk) we will *not* make such assumptions

Problem formulation

- canonical problem formulation:

$$\text{minimize } \sum_{k=0}^K l(\mathbf{y}(t_k), \hat{\mathbf{y}}_k(t_k))$$

$$\text{subject to } \hat{\mathbf{y}}_k(t_k) = g_k(\mathbf{x}(t_k), \mathbf{x}(t_{k-1}), \dots, \mathbf{y}(t_{k-1}), \mathbf{y}(t_{k-2}), \dots)$$

where

- $g_0, g_1, \dots : \mathcal{D} \rightarrow \mathbf{R}^m$ are optimization variables,
- $\mathcal{D} = \mathbf{R}^n \times \mathbf{R}^n \times \dots \times \mathbf{R}^m \cup \{\text{null}\} \times \mathbf{R}^m \cup \{\text{null}\} \times \dots$ is domain of g_k ,
- $l : \mathbf{R}^m \times \mathbf{R}^m \rightarrow \mathbf{R}_+$ is loss function
- assume that for some k , no label is given, *i.e.*, $\mathbf{y}(t_k) = \text{null}$
- one way to exploit all the information is to use *online learning*, *i.e.*, g_k is updated (or not) for every step, k

ML solution candidates

- ignore temporal dependency and predict $y(t_k)$ from $x(t_k)$, $\hat{y}_k(t_k) = g(x(t_k))$
 - supervised learning such as tree algorithms (*e.g.*, random forest)
 - classical statistical learning (*e.g.*, partial least squares),
 - boosting algorithms (*e.g.*, gradient boosting, XGBoost)
 - MLP, DNN, *etc.*
- use sequential learning methods
 - recurrent neural network (RNN), long short-term memory (LSTM)
 - Transformer-type approaches (using attention mechanism)

Difficulties with manufacturing applications

- for many manufacturing applications
 - covariate shift and concept drift exist:
 - * $p(x(t_k), x(t_{k-1}), \dots)$ changes over time
 - * $p(y(t_k)|x(t_k), x(t_{k-1}), \dots, y(t_{k-1}), y(t_{k-2}), \dots)$ changes over time
 - hence, traditional off-line training *doesn't* work!

One Solution - prediction based on experts' advice

- assume p_k experts: $f_{i,k} : \mathbf{R}^n \rightarrow \mathbf{R}^m$ ($i = 1, 2, \dots, p_k$) for each time step, t_k
 - $f_{i,k}$ can be DNN, (online) ridge regression, or other statistical learning algorithms
- model predictor at time step k , $g_k : \mathbf{R}^n \rightarrow \mathbf{R}^m$ as weighted sum of experts:

$$g_k = w_{1,k}f_{1,k} + w_{2,k}f_{2,k} + \dots + w_{p_k,k}f_{p_k,k} = \sum_{i=1}^{p_k} w_{i,k}f_{i,k}$$

- online learning and inferencing procedure:
 - if $y(t_k) \neq \text{null}$, *i.e.*, new observation available, update $f_{i,k}$ and $w_{i,k}$
 - if $y(t_k) = \text{null}$, *i.e.*, no observation is available, predict $\hat{y}_k(t_k) = g_k(x(t_k))$

Algorithm description

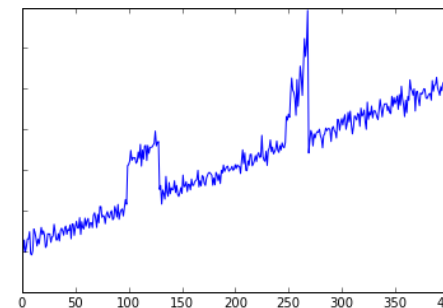
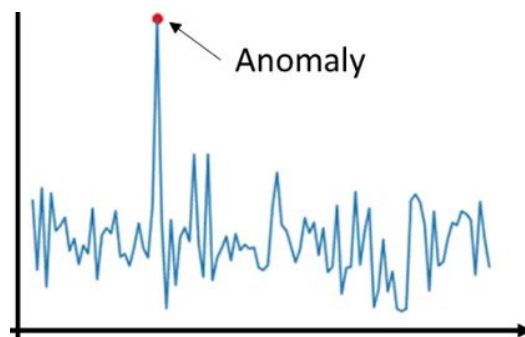
- set $k = 0$
 - given $(x(t_k), y(t_k))$, predict $\hat{y}_{i,k}(t_k) = f_{i,k}(x(t_k))$
 - * if $y(t_k) \neq \text{null}$
 - predict $\hat{y}(t_k) = y(t_k)$
 - update $f_{i,k} \rightarrow f_{i,k+1}$ based on $(x(t_k), y(t_k))$
 - update $w_{i,k} \rightarrow w_{i,k+1}$ based on prediction error, $y(t_k) - \hat{y}_{i,k}(t_k)$
 - * if $y(t_k) = \text{null}$
 - predict $\hat{y}(t_k) = g_k(x(t_k)) = \sum_{i=1}^p w_{i,k} \hat{y}_{i,k}(t_k)$
 - update $f_{i,k+1} := f_{i,k}$ (not update)
 - update $w_{i,k+1} := w_{i,k}$ (not update)
- update $k := k + 1$ and repeat

What about unlabelled data?

- semi-supervised learning
- representation learning
- extension of model update rules for unlabelled data - for some statistical learning methods
- *NO* right answer for this! Multiple projects led to one success!
 - pre-cost-benefit analysis strongly recommended (or even *must-do*)

TS anomaly detection

- three types of anomaly detection: given TS $x : T \rightarrow \mathbf{R}^n$
 - point anomaly: find k such that $x(t_k)$ is considerably different from most of the other data
 - segment anomaly: find k_1 and k_2 such that TS segment $x(t_k)|_{k=k_1}^{k_2}$ is considerably different from most of the other data
 - sequence anomaly: given $x_1, \dots, x_n : T \rightarrow \mathbf{R}$, find x_i such that it is considerably different from the other TS, *i.e.*, x_j ($j \neq i$)



A TS segment anomaly detection algorithm

- one method investigated using classification: given $x(t_j)|_{j=k}^{k-l+1}$, (segment of length l)
 - training:
 - * choose one classifier, c , and p feature extractors (or transformers): f_i
 - * for each k
 - extract p features by applying extractors: $y_{i,k} = f_i \left(x(t_j)|_{j=k-l+1}^k \right)$
 - train the classifier, c , with training data: $(y_{1,k}, 1), (y_{2,k}, 2), \dots, (y_{p,k}, p)$,
 - inferencing:
 - * given new segment $x(t_j)|_{j=k-l+1}^k$, apply c to the extracted features, $y_{i,k}$
 - * if they are substantially different from $(1, 2, \dots, p)$, declare it's anomaly
 - “difference” quantified by some *anomaly score* defined using, *e.g.*, KL divergence or entropy

Prediction of uncertainty of prediction

- every point prediction is wrong!
 - $\text{Prob}(\hat{Y}_k = Y_k) = 0$
- more importantly, want to know how reliable our prediction is
 - *FEW* literature deals with this
 - *NO* research done for exact solution
- critical for our customers, *i.e.*, *downstream applications*
 - in reality, way more important than algorithm accuracy
- we call this method of *predicting of uncertainty of predictive* model uncertainty estimation (MUE)

Model uncertainty estimation (MUE)

- multiple ways to measure this:

(1) probability of true value falling into an interval: for fixed $a > 0$

$$\mathbf{Prob}(|Y_k - \hat{Y}_k| < a) = \mathbf{Prob}(Y_k \in (\hat{Y}_k - a, \hat{Y}_k + a))$$

(2) predictive distribution size: find $a > 0$ such that

$$\mathbf{Prob}(|Y_k - \hat{Y}_k| < a) = 90\%, \text{ e.g.}$$

(3) distribution of Y_k : find PDF of Y_k

- solving (3) readily solves (1) and (2)

MUE for expert-based online learning

- reminder: online learning method based on expert advice is given by

$$g_k = w_{1,k}f_{1,k} + w_{2,k}f_{2,k} + \cdots + w_{p,k}f_{p,k} = \sum_{i=1}^p w_{i,k}f_{i,k}$$

- assume that $f_{i,k}$ is parameterized by $\theta_{i,k}$
- if we can calculate $p(\theta_{i,k})$
 - can evaluate the *predictive distribution*

$$p_{i,k}(y(t_k); x(t_k)) = \int p(y; x(t_k), \theta_{i,k})p(\theta_{i,k})d\theta_{i,k}$$

- problem to solve: evaluate distribution of g_k given $p_{i,k}$

MUE for expert-based online learning

- independent case: if $p_{1,k}, \dots, p_{p,k}$ are (statistically) independent, then PDF of $g_k(x(t_k))$ can be calculated by

$$\frac{p_{1,k}(y/w_{1,k}; x(t_k))}{w_{1,k}} \star \dots \star \frac{p_{p,k}(y/w_{p,k}; x(t_k))}{w_{p,k}}$$

- Gaussian case: $p_{1,k}, \dots, p_{p,k}$ are Gaussians with correlation coefficient matrix R , *i.e.*,

$$p_{i,k} \sim \mathcal{N}(\mu_{i,k}, \sigma_{i,k}^2)$$

$$R = \begin{bmatrix} 1 & \rho_{1,2} & \rho_{1,3} & \cdots & \rho_{1,p} \\ \rho_{1,2} & 1 & \rho_{2,3} & \cdots & \rho_{2,p} \\ \rho_{1,3} & \rho_{2,3} & 1 & \cdots & \rho_{3,p} \\ \vdots & \vdots & \vdots & \ddots & \vdots \\ \rho_{1,p} & \rho_{2,p} & \rho_{3,p} & \cdots & 1 \end{bmatrix} \in \mathbf{R}^{p \times p}$$

- then g_k is also Gaussian

$$\mathcal{N}(w_k^T \mu_k, w_k^T \text{diag}(\sigma_k) R \text{diag}(\sigma_k) w_k)$$

where

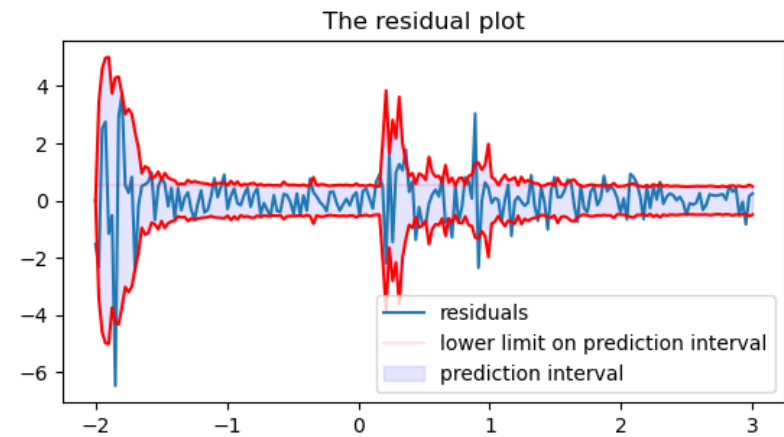
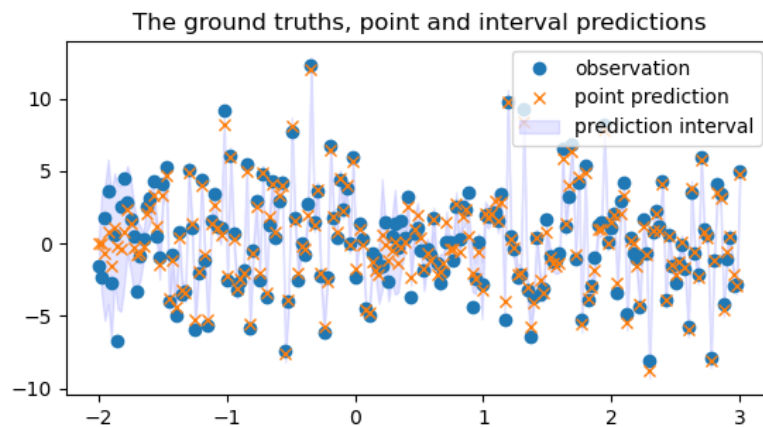
$$w_k = [w_{1,k} \quad \cdots \quad w_{p,k}]^T \in \mathbf{R}^p$$

$$\mu_k = [\mu_{1,k}(x(t_k)) \quad \cdots \quad \mu_{p,k}(x(t_k))]^T \in \mathbf{R}^p$$

$$\sigma_k = [\sigma_{1,k}(x(t_k)) \quad \cdots \quad \sigma_{p,k}(x(t_k))]^T \in \mathbf{R}^p$$

MUE application example

- observe
 - initially the predictor is *not sure* about its prediction
 - after a while, the *credibility interval* converges to its performance limit
 - as soon as shift happens, credibility interval increases (as it should be)
- this information is *crucial for downstream applications*, e.g., process control



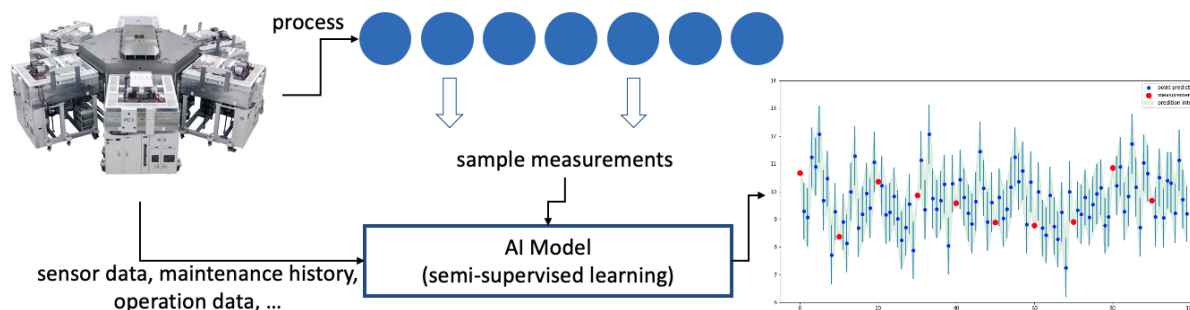
TS Learning Applications in Manufacturing

Virtual metrology (VM)

- in many cases, we cannot measure all processed materials for fundamental reasons
 - measurement equipment is too expensive
 - no room in the factory for many measurement equipment
 - measuring every materials hinders production speed inducing low throughput
- thus, we do sampling (with very low sampling rate)
 - in semiconductor manufacturing line, average sampling rate is less than 1%
- problem: we want to predict the measurement of unmeasured material using indirect signals such as
 - sensor data, maintenance history, operation data, . . .

VM

- difficulties
 - covariate shift and concept drift due to, *e.g.*, preventive maintenance, chamber contamination, *etc.*
 - hence, data becomes stale quickly
- **online learning method based on expert advice** can be used for the solution
- MUE provides the uncertainty level of our prediction, *i.e.*, *credibility intervals*
 - process engineers can judge when they can trust the predictions by how much
 - we can monitor performance degradation



Applications of VM

- why do we even develop VM?
- focus on the values we deliver to our customers; want VM to be used for
 - process (feedback) control → average matters
 - detecting equipment out-of-control status → anomalies matters
 - detecting root causes for yield drop
 - predicting (future) yield

Different error measures depending on VM applications

- mean-square-error (MSE) for run-to-run control (where \mathcal{K} is test index set)

$$- \sqrt{\sum_{k \in \mathcal{K}} (y(t_k) - \hat{y}(t_k))^2 / |\mathcal{K}|}$$

- mean-p-norm-error (MPE) for anomaly detection (for some $p > 2$)

$$- \left(\sum_{k \in \mathcal{K}} |y(t_k) - \hat{y}(t_k)|^p / |\mathcal{K}| \right)^{1/p}$$

- soft-max error (SME) for anomaly detection (for some $\alpha > 0$)

$$- \log \left(\sum_{k \in \mathcal{K}} \exp(\alpha \|y(t_k) - \hat{y}(t_k)\|_1) \right) / \alpha$$

- R-squared (R^2)

$$- 1 - \frac{\sum_{k \in \mathcal{K}} (y(t_k) - \hat{y}(t_k))^2}{\sum_{k \in \mathcal{K}} (y(t_k) - \bar{y})^2}$$

Root cause analysis by anomaly detection

- background: statistical process control (SPC)
 - conventional old method used in manufacturing (since 1950's)
 - monitor measurement and alert when things go wrong
 - things go wrong defined by rules; examples:
 - * measument out of $(\mu - 3\sigma, \mu + 3\sigma)$,
 - * three consecutive measurements out of $(\mu - 2\sigma, \mu + 2\sigma)$
- our problem: when SPC alarm goes off, find the responsible (chamber in) equipment

Root cause analysis by anomaly detection

- two methods exist: (1) segment anomaly detection and (2) sequence anomaly detection
- two types of data exist: (1) sensor data and (2) processed material measurement data
- problems: given TS data $x_e(t_0), x_e(t_1), \dots$ for each entity $e \in E$ (entity refers to equipment, chamber, station, *etc.*)
 - find entity e that shows abnormal behavior using segment anomaly detection
 - find entity e that is different from other entities using sequence anomaly detection

What really matter in real software productionization

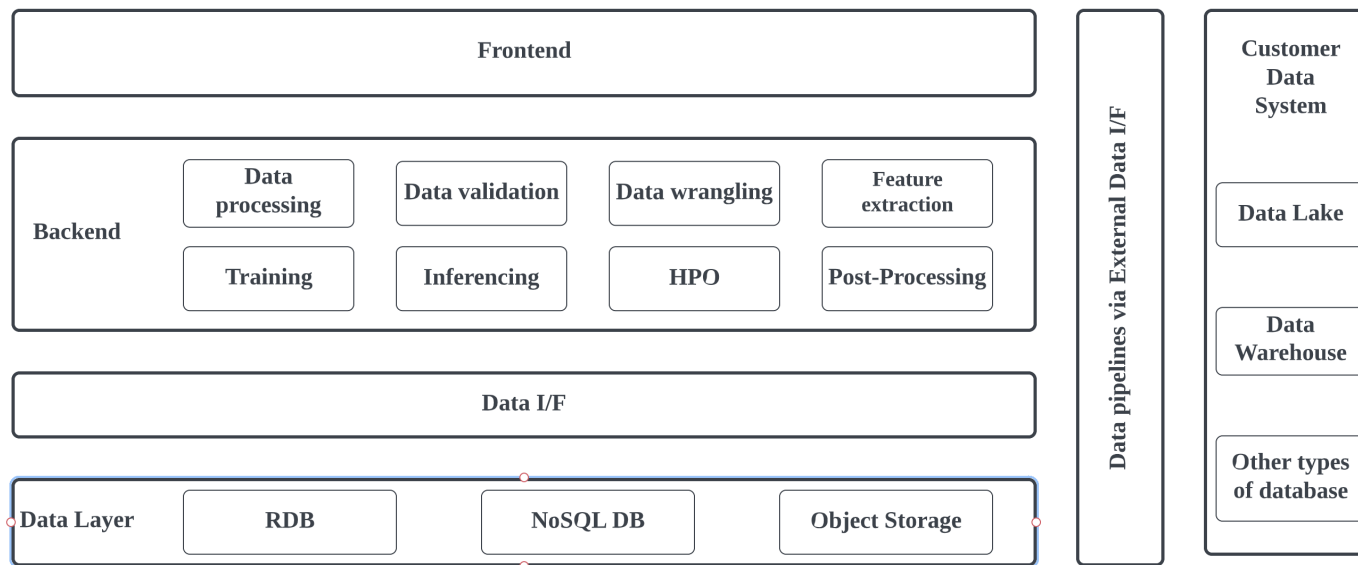
- MLOps
- data preprocessing - missing values, inconsistent predictor names, difference among equipment manufacturers
- feature extraction & selection
- monitoring & retraining
- notification, *e.g.*, messengers & emails
- automatic mechanism vs. by human inspection and approval
- data base, data latency, data reliability, & data availability

⇒ Excellency in software system design and development using public or on-premise cloud systems

Manufacturing AI Software System Development

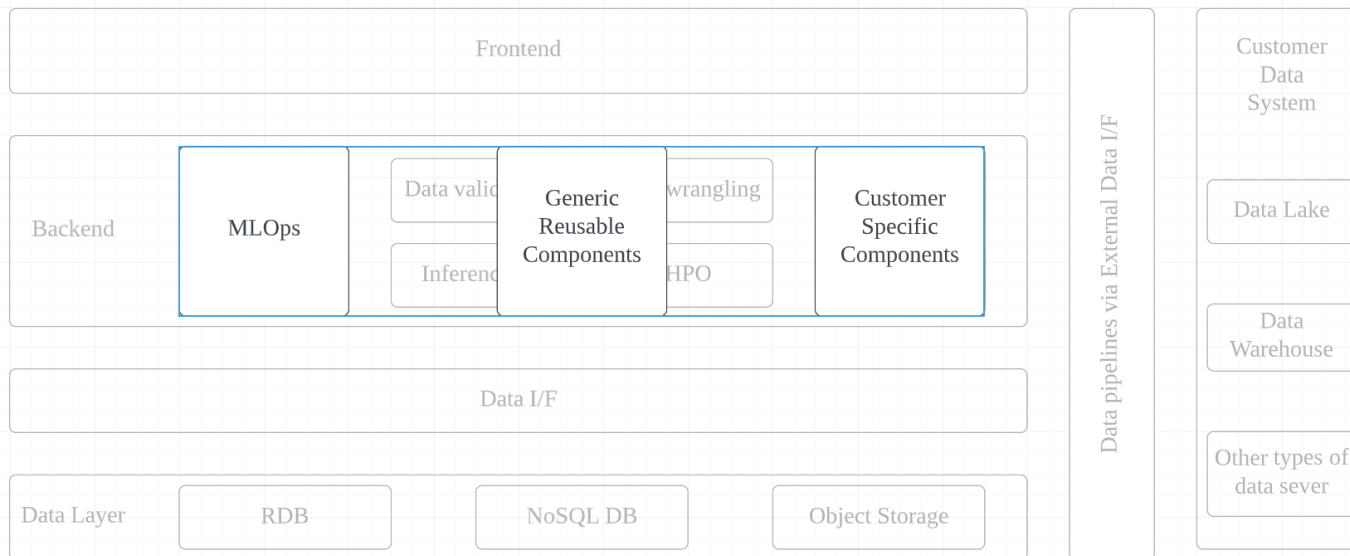
Manufacturing AI Software System

- frontend / backend / data layers with interfaces
- external IFs for data pipelines (with security considerations)
- development environment should be built separately



Reusable components vs customer specific components

- make sure to have two separate components; generic reusable and customer specific
- generic models should be tuned for each customer (or use cases)
- generic model library grows as interacting with more and more customers



Conclusion

- TS learning and anomaly detection occur at various places in manufacturing AI applications
- concept drift and data noise make them very challenging, but have working solutions
- solutions: TS supervised learning, TS anomaly detection, model uncertainty estimation
- real bottlenecks in reality
 - data quality, preprocessing, monitoring, notification, and retraining
 - data latency, availability, and reliability
 - excellency in software platform design and development using cloud services

Thank You! - sunghee.yun@gmail.com